

## EAST Search History

Ref #	Hits	Search Query	Dbs	Default Operator	Plurals	Time Stamp
S1	704	451/56.ccts.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 10:37
S2	478	451/50.ccts.	US-PGPUB; OR USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 10:37
S3	254722	polish\$3	US-PGPUB; OR USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 10:38
S4	2208	451/41.ccts. and polish\$3	US-PGPUB; OR USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 10:38
S5	480	451/56.ccts. and polish\$3	US-PGPUB; OR USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 10:38
S6	380	451/50.ccts. and polish\$3	US-PGPUB; OR USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 10:39
S7	419839	pad	US-PGPUB; OR USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 10:39
S8	46	"3-hydroxy-4-pyrone"	US-PGPUB; OR USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:04
S9	955901	("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane borohydrides (dialkylamine adj acid) formalddehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trihydroxybenzene (solvated adj electrons) (sulfurous adj acid)	US-PGPUB; OR USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:15

## EAST Search History

S10	955901	("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or dialkylamine adj boranes or formaldehyde or (formic adj acid) or hydrogen or hydroquinones or hydroxylamine or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid) ("428" or "156" or "51").clas.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:17
S11	303143		US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:18
S12	43264	((("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane borohydrides (dialkylamine adj boranes) formalddehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trihydroxybenzene (solvated adj electrons) (sulfurous adj acid)) and ((("428" or "156" or "51").clas.)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:18
S13	0	"451.clas"	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:18
S14	64433	"451".clas.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:18
S15	1097	((("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane borohydrides (dialkylamine adj boranes) formalddehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trihydroxybenzene (solvated adj electrons) (sulfurous adj acid)) and ("51").clas.) reducing agent	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:19
S16	2868440		US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:23

### EAST Search History

S17	834	((("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane borohydrides (dialkylamine adj boranes) formaldehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trihydroxybenzene (solvated adj electrons) (sulfurous adj acid) and ("451 :clas.) and (reducing agent) (451/41.ccls. and polish\$3) and pad	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:23
S18	1562	(451/56.ccls. and polish\$3) and pad	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:34
S19	396	(451/56.ccls. and polish\$3) and pad	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:31
S20	263	(451/60.ccls. and polish\$3) and pad	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:31
S21	337	((("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane borohydrides (dialkylamine adj boranes) formaldehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trihydroxybenzene (solvated adj electrons) (sulfurous adj acid) and ((451/41.ccls. and polish\$3) and pad) or ((451/56.ccls. and polish\$3) and pad) or ((451/60.ccls. and polish\$3) and pad))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:42

### EAST Search History

S22	49	((("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane borohydrides (dialkylamine adj boranes) formaldehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trihydroxybenzene (solvated adj electrons) (sulfurous adj acid) and ((451/41.ccls. and polish\$3) and pad) or ((451/56.ccls. and polish\$3) and pad) or ((451/60.ccls. and polish\$3) and pad) or ((451/41.ccls. and polish\$3) and pad))) not (((451/41.ccls. and polish\$3) and pad) and (((("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane borohydrides (dialkylamine adj boranes) formaldehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trihydroxybenzene (solvated adj electrons) (sulfurous adj acid) and ((451/41.ccls. and polish\$3) and pad) or ((451/56.ccls. and polish\$3) and pad) or ((451/60.ccls. and polish\$3) and pad) or ((451/41.ccls. and polish\$3) and pad)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:35
S23	288	((("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane borohydrides (dialkylamine adj boranes) formaldehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trihydroxybenzene (solvated adj electrons) (sulfurous adj acid) and ((451/41.ccls. and polish\$3) and pad) or ((451/56.ccls. and polish\$3) and pad)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/01/24 13:20
S24	93	((("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane borohydrides (dialkylamine adj boranes) formaldehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trihydroxybenzene (solvated adj electrons) (sulfurous adj acid) and ((451/41.ccls. and polish\$3) and pad) or ((451/56.ccls. and polish\$3) and pad)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 13:38

### EAST Search History

S25	288	((“3-hydroxy-4-pyrones”) or (hydroxy adj1 butyrolactones) or borane borohydrides (dialkylamine adj boranes) formaldehyde (formic adj acid) hydrogen hydroquinones hydroxylamine (hypophosphorous adj acid) trihydroxybenzene (sulfurous (isolated adj electrons) (sulfurous adj acid) ) and ((451/41.ccls. and polish\$3) and pad) oxidizes\$4 and abrasive and polish\$4	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2006/02/14 15:39
S26	3038	1 oxidizes2 and abrasive and polish\$4 and (reducing adj agent) and ((liquid or aqueous) adj carrier)	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 14:22
S27	527	12 (“4769046”   “5489233”   “5527423”   “59358794”   “6010269”   “6015056”   “6062968”   “61170010”   “6117783”   “6126532”   “6290736”   “6299795”   “2002/0004366”   “2002/0010232”   “2002/0017630”),PN.	USPAT	OR	OFF	2004/09/22 14:18
S28	77604	tantalum	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 14:22
S29	2905	451/41.ccls.	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 14:23
S30	531	190 tantalum and 451/41.ccls.	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2004/09/22 14:23
S31	895	\$1-alumina or alpha-alumina or (alpha near alumina)) with abrasive	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/01/21 15:29
S32	0	“451.clas”	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/01/21 15:11

### EAST Search History

S34	64929	*451*.clas,	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/01/21 15:12
S35	66	S32 and S34	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/01/21 16:01
S36	6947	(silica or (fumed adj alumina)) with abrasive	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/01/21 15:30
S37	1138	(S32 or S36) and S34	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/01/21 15:30
S38	11	S35 and (reducing adj agent)	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/01/21 15:31
S39	27	S37 and (reducing adj agent)	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/01/21 15:31
S40	1109	S36 and S34	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/01/21 16:01
S41	24	S40 and (reducing adj agent)	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/01/21 16:01
S42	2	“6454822”.pn.	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/01/24 09:38
S43	64929	*451*.clas,	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/01/24 10:45
S44	195	S43 and ((iridium adj oxide) or (tantalum same (oxidized, oxide, oxidizer))) and ((polishing adj pad or abrasive))	US-PPGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/01/24 10:48

### EAST Search History

S#	#	Search Query	Start Date	End Date	OFF	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT
S45	195	S43 and ((iridium adj oxide) or (tantalum same (oxidized, oxide, oxidizer)) and ((polishing adj pad) or abrasive))	2005/01/24 09:58	2005/01/24 09:58	OFF	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT
S46	6	(US-20020182982-\$ or US-20030013387-\$ or US-20040023495-\$ or US-20040132385-\$) did, or (US-6454822-\$ or US-6709316-\$). did.	2005/01/24 09:59	2005/01/24 09:59	OFF	US-PGPUB; USPAT
S47	2	S45 and S46	2005/01/24 10:08	2005/01/24 10:08	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S48	37	(silicone adj oxide) with "Si"	2005/01/24 11:17	2005/01/24 11:17	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S49	6851	silicone near4 metal	2005/01/24 10:15	2005/01/24 10:15	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S50	2832	silicone near2 metal	2005/01/24 10:15	2005/01/24 10:15	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S51	740	silicone near1 metal	2005/01/24 10:15	2005/01/24 10:15	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S52	1	S43 and S51	2005/01/24 10:15	2005/01/24 10:15	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S53	5	S43 and S50	2005/01/24 10:16	2005/01/24 10:16	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT

### EAST Search History

S#	#	Search Query	Start Date	End Date	OFF	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT
S54	11	S43 and S49	2005/01/24 10:16	2005/01/24 10:16	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S55	10	S54 not S51	2005/01/24 10:17	2005/01/24 10:17	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S56	6	S54 not S53	2005/01/24 10:23	2005/01/24 10:23	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S57	0	S47 and (iridium adj oxide)	2005/01/24 10:24	2005/01/24 10:24	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S58	2	S43 and (iridium adj oxide)	2005/01/24 10:47	2005/01/24 10:47	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S59	212721	"428".clas.	2005/01/24 10:46	2005/01/24 10:46	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S60	609	(substrate or wafer or semiconductor or semi-conductor) with (iridium adj oxide)	2005/01/24 10:49	2005/01/24 10:49	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S61	2	S43 and (iridium adj oxide)	2005/01/24 10:49	2005/01/24 10:49	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S62	15	((substrate or wafer or semiconductor or semi-conductor) with (iridium adj oxide)) and ((polishing adj pad) or abrasive)	2005/01/24 10:50	2005/01/24 10:50	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT
S63	1388	(copper adj oxide) with "Cu"	2005/01/24 11:17	2005/01/24 11:17	OFF	US-PGPUB; OR USPAT; USOCR; EPO; JPO; DERWENT

### EAST Search History

S64	8	S63 and S43	US-PGPUB; OR	OFF	2005/01/24 11:17
S65	665	(Iridium adj oxide) and (polish polishing CMP ("chemical mechanical polishing"))	US-SPAT; USOCR; EPO; JPO; DERWENT	OFF	2005/01/24 13:23
S66	44	S65 and (reducing adj agent)	US-PGPUB; OR	OFF	2005/01/24 13:23
S67	569	(Iridium adj oxide) and (CMP or ("chemical mechanical polishing"))	US-SPAT; USOCR; EPO; JPO; DERWENT	OFF	2005/01/24 13:24
S68	569	(Iridium adj oxide) and (CMP or ("chemical mechanical polishing"))	US-PGPUB; OR	OFF	2005/01/24 13:24
S69	46	(Iridium adj oxide) same (CMP or ("chemical mechanical polishing"))	US-SPAT; USOCR; EPO; JPO; DERWENT	OFF	2005/01/24 14:09
S70	2	"4717581".pn.	US-PGPUB; OR	OFF	2005/01/24 14:09
S71	2	"4679572".pn.	US-SPAT; USOCR; EPO; JPO; DERWENT	OFF	2005/01/24 14:11
S72	2567	451/41.ccls. and polish\$3	US-PGPUB; OR	OFF	2005/07/12 10:33
S73	550	451/56.ccls. and polish\$3	US-SPAT; USOCR; EPO; JPO; DERWENT	OFF	2005/07/12 10:33
S74	427	451/60.ccls. and polish\$3	US-PGPUB; OR	OFF	2005/07/12 10:33

### EAST Search History

S75	80	(S72 S73 S74) and ("ph" near2 (buffering buffer buffer\$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/07/12 10:43
S76	266	(S72 S73 S74) and (surfactant)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/07/12 10:55
S77	1183	(ammonium adj hydroxide) same ("ph" near2 (buffering buffer buffer\$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/07/12 10:43
S78	366	(ammonium adj hydroxide) with ("ph" near2 (buffering buffer buffer\$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/07/12 10:44
S79	105	(ammonium adj hydroxide) near4 ("ph" near2 (buffering buffer buffer\$4))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/07/12 10:44
S80	2	(S72 S73 S74) and ((advantages advantageous advantag\$5) with surfactant)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/07/12 10:56
S81	5	("451".clas.) and ((advantages advantageous advantag\$5) with surfactant)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/07/12 11:00
S82	40	("451".clas.) and ((desired improve improved improvement) with surfactant)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/07/12 11:05
S83	2	"5783 489".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/07/12 11:05

## EAST Search History

S84	3 (polishing adj (pad pads)) and (CMP or "chemical mechanical polishing" or "chemical mechanical planarization") and (reducing adj agent) with (hydroxylamine and ("3-hydroxy-4-pyrone") or (hydroxylamine adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2006/02/14 16:29
S85	3 (polishing adj (pad pads)) and (CMP or "chemical mechanical polishing" or "chemical mechanical planarization") and (reducing adj agent) with (hydroxylamine with ("3-hydroxy-4-pyrone") or (hydroxylamine adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2006/02/14 15:44

## EAST Search History

S87	3 (polishing adj (pad pads)) and (reducing adj agent) with ((hydroxylamine with ("3-hydroxy-4-pyrone") or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid))))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2006/02/14 15:45
S88	5 (CMP or "chemical mechanical polishing" or "chemical mechanical planarization") and ((reducing adj agent) with (hydroxylamine and ("3-hydroxy-4-pyrone") or (hydroxylamine adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid))))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2006/02/14 16:56

## EAST Search History

## EAST Search History

S90	176	(wafer polish planarize substrate copper) and ((reducing adj agent) with (hydroxylamine and ("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; OR USPAT; EPO; JPO; DERWENT	OFF	2006/02/14 15:49
S91	185	(semiconductor polish planarize substrate copper) and ((reducing adj agent) with (hydroxylamine and ("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; OR USPAT; EPO; JPO; DERWENT	OFF	2006/02/14 15:49
S92	185	(semiconductor planarize substrate copper) and ((reducing adj agent) with (hydroxylamine and ("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; OR USPAT; EPO; JPO; DERWENT	OFF	2006/02/14 15:49
S93	185	(semiconductor substrate copper) and ((reducing adj agent) with (hydroxylamine and ("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; OR USPAT; EPO; JPO; DERWENT	OFF	2006/02/14 15:56

## EAST Search History

S98	345	((polishing adj (pad pads)) or (CMP or "chemical mechanical polishing" or "chemical mechanical planarization") and ((reducing adj agent) with ("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; OR USPAT; EPO; JPO; DERVENT	OFF	2006/02/14 16:51	
S99	308	((polishing adj (pad pads)) or (CMP or "chemical mechanical polishing" or "chemical mechanical planarization") and ((slurry composition solution) and (reducing adj agent) with ("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; OR USPAT; EPO; JPO; DERVENT	OFF	2006/02/14 16:46	
S10	223	((polishing adj (pad pads)) or (CMP or "chemical mechanical polishing" or "chemical mechanical planarization") and ((slurry composition) and ((reducing adj agent) with ("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; OR USPAT; EPO; JPO; DERVENT	OFF	2006/02/14 16:51	
S10	214	((polishing adj (pad pads)) or (CMP or "chemical mechanical polishing" or "chemical mechanical planarization") and ((reducing adj agent) with ("3-hydroxy-4-pyrone") or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; OR USPAT; EPO; JPO; DERVENT	OFF	2006/02/14 16:51	
S10	4	((3-hydroxy-4-pyrone) or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; OR USPAT; EPO; JPO; DERVENT	OFF	2006/02/14 16:57	
S10	4	((3-hydroxy-4-pyrone) or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; OR USPAT; EPO; JPO; DERVENT	OFF	2006/02/14 17:17	

## EAST Search History

S10 4	0	(CMP or "chemical mechanical polishing" or "chemical mechanical planarization") and ((reducing adj agent) with (glucose sulfonate (potassium adj iodide)) with (((3-hydroxy-4-pyrone*) or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2006/02/14 16:57
S10 5	46	((polishing adj (pad pads)) or planarite planarization slurry) and ((reducing adj agent) with ((glucose sulfonate (potassium adj iodide)) with (((3-hydroxy-4-pyrone*) or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2006/02/14 17:01

## EAST Search History

S10 7	105	(CMP or "chemical mechanical polishing" or "chemical mechanical planarization") and (hydroxylamine with ((3-hydroxy-4-pyrone*) or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2006/02/14 17:49
S10 8	105	(CMP or "chemical mechanical polishing" or "chemical mechanical planarization") and (hydroxylamine with ((3-hydroxy-4-pyrone*) or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2006/02/14 17:48
S10 9	81	(CMP or "chemical mechanical polishing" or "chemical mechanical planarization") and (hydroxylamine with ((3-hydroxy-4-pyrone*) or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydrogen or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid) or not (hydrogen adj peroxide)))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2006/02/14 17:53
S11 0	24	S107 not S109	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2006/02/14 17:49

## EAST Search History

S11 1	31	(CMP or "chemical mechanical polishing" or "chemical mechanical planarization") and (hydroxylamine with ("3-hydroxy-4-pyrones") or (hydroxy adj1 butyrolactones) or borane or borohydrides or (dialkylamine adj borane\$3) or formaldehyde or (formic adj acid) or hydroquinone\$3 or (hypophosphorous adj acid) or trihydroxybenzene or (solvated adj electrons) or (sulfurous adj acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2006/02/14 17:53
S11 2	339	(complexing adj agent) with (chelating adj agent)	US-PGPUB; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/15 08:55
S11 3	1	10/753138.app.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/15 09:20
S11 4	32	("20020039839" "200200908201" "20020102923" "2002111027" "2003013387" "20030119319" "5489233" "5527423" "5691219" "5958794" "6117783" "6139763" "6274063" "6313039" "6315803" "6419354" "6327622");PN_109/755717.app.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/15 09:28
S11 5	1	09/755717.app.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/15 09:28